

## PATENT ABSTRACTS OF JAPAN

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## (54) POSITIVE TYPE RESIST COMPOSITION

## (57)Abstract:

PROBLEM TO BE SOLVED: To provide a positive type resist composition having excellent SEM resistance and resolution and further having improved defocus latitude.

SOLUTION: The positive type resist composition contains: a blend of two or more resins each having a specified lactone monomer unit and having a velocity of dissolution in an alkali developing solution increased by the action of an acid; and a compound which generates the acid when irradiated with active light or radiation.

## LEGAL STATUS

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